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Amendments to the Specification:

Please replace the title with the following amended title:

ELECTRON BEAM DEPICTING METHOD, PRODUCTION METHOD OF MOTHER DIE, MOTHER DIE, PRODUCTION METHOD OF METALLIC MOLD, METALLIC MOLD, OPTICAL ELEMENT AND ELECTRONIC BEAM DEPICTING APPARATUS

A METHOD FOR DEPICTING A DIFFRACTION STRUCTURE ON A SUBSTRATE USING AN ELECTRON BEAM

Page 1, replace the first and second paragraphs with the following amended paragraphs:

The present invention relates to a depicting technology by an electron beam, and particularly to a depicting technology by which, onto a base material which is a depicted object, a predetermined pattern, for example, a diffraction pattern corresponding to an optical element is depicted on a base material.

Conventionally, a CD and a DVD CD's and DVD's are widely used as [[an]] information recording medium, and for a. These require precision equipment such as a reading apparatus by which

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the information is read, in which from these recording media, many optical elements are used.

Page 1, replace the third paragraph, bridging pages 1-2,
with the following amended paragraphs:

Recently, [[a]] the specification or performance required for these optical elements is improved increased, and particularly, [[in a]] for the pick-up lens for a recording medium such as the DVD, to an because of an increase [[of a]] in the recording density[[,]]. These lenses use a diffraction structure and it is therefore required that a more accurate diffraction structure is formed. Specifically, a processing accuracy in a scale smaller than a wavelength of the light, for example, sub-10 nm scale, is required.

Page 2, replace the third full paragraph with the following
amended paragraph:

Up to now, the molding die is processed by a common usual engineering, for instance example, a cutting bit bite of processing engineering, however, However, when [[the]] a fine

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shape such as a [[such]] diffraction structure is to be formed, the processing accuracy is poor, and there is a limit in the strength or life of the bit bite, and it. It is therefore difficult that the for accurate processing in the sub-micron order or in the level more accurate than that, to be [[is]] conducted.

Page 4, replace the penultimate paragraph with the following amended paragraph:

Hereupon, in the case of the optical element such as an [[OD]] CD lens, in the depicting process, because the processing accuracy in the level within several 10 s nm to the designed value is required, it is a very difficult target to realize the [[more]] greater accuracy.

- Page 7, replace the first full paragraph with the following amended paragraph:
- (6) The method of item 1, wherein the contour of the substrate, onto which the diffraction gratings are depicted, is a carved curved surface.